



U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				ATTY. DOCKET NO. MI22-2347	Priority SERIAL NO. 10/039,456			
				APPLICANT Ying Huang et al.				
				FILING DATE		GROUP		
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name		Class	Subclass	Filing Date If Appropriate
YN	AA	5,946,601	8/99	Wong et al.				
	AB	6,033,979	3/00	Endo				
	AC	6,037,664	3/00	Zhao et al.				
	AD	6,046,104	4/00	Kepler				
	AE	6,057,417	5/00	Arnold et al.				
	AF	6,234,657 B1	09/01	Chooi et al.				
	AG	5,122,483	06/92	Sakai et al.				
	AH	6,265,779 B1	07/01	Grill et al.				
	AI	6,410,437 B1	06/25/02	Flanner et al.				
	AJ							
	AK							
	AL							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AM							
	AN							
	AO							
	AP							
	AQ							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
YN	AR		Balliga, John, "Options for CVD of Dielectrics Include Low-k Materials," Semiconductor International June 1998, pp. 1-6					
	AS		Singer, Peter, "Dual-Damascene Challenges Dielectric-Etch," Semiconductor International August 1999, pp. 1-5					
	AT							
EXAMINER	JOSEPH NGUYEN			DATE CONSIDERED		9/21/04		

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

BEST AVAILABLE COPY